#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
All Times are local time in Boston, MA, USA (EDT)									
On June 21-22, 2025 Short Courses are on-line only. From June 23-26, 2025 the workshop is in-person only.									
Version: May 3, 2025 . For questions or comments please contact info@euvlitho.com									
Short Course									
Short Course: EUV and Soft X-Ray Sources									
8:30 AM, Saturday, June 21, 2025, Boston, MA (Course is held online Only)									
All Times are for Boston, MA, USA. Please estimate times for your own time zones, for this live event.									
Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn, Dinh Nguyen and Ladislav Pina									
Short Courses and EUVL & Source Workshop require separate registrations. Please visit www.euvlitho.com for information.									
						AV Test and Speaker Check-in	0:15	8:30 AM	8:45 AM
	1	Gerry	O'Sullivan	UCD		Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics	1:30	8:45 AM	10:15 AM
						Break	0:15	10:15 AM	10:30 AM
	2	Marcelo	Ackerman	University of Twente		EUV Multilayers	1:30	10:30 AM	12:00 PM
						Lunch Break	0:30	12:00 PM	12:30 PM
	3	Henry	Kapteyn	Univ of Colorado and K&M Labs		Fundamentals and Applications of Coherent High Harmonic EUV Sources	1:30	12:30 PM	2:00 PM
						Break	0:15	2:00 PM	2:15 PM
	4	Dinh	Nguyen	xLight		Module 5: FEL for EUV Lithography	1:30	2:15 PM	3:45 PM
						Break	0:15	3:45 PM	4:00 PM
	5	Ladislav	Pina	CTU in Prague		Grazing Incidence Optics and Applications for EUV and Soft X-ray Sources	1:30	4:00 PM	5:30 PM
Short Course Adjourned									

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
						Short Course			
						***Short Course:* EUV Lithography**			
						8:30 AM, Sunday, June 22, 2025, Boston, MA (Course is held online Only)			
						All Times are for Boston, MA, USA. Please estimate times for your own time zones, for this live event.			
						Instructors: Vivek Bakshi (EUV Litho, Inc.), Patrick Naulleau (CXRO), Sangsul Lee (Postech University), and Jan van Shoot (ASML)			
						Short Courses and EUVL & Source Workshop require separate registrations. Please visit www.euvlitho.com for information.			
						AV Test and Speaker Check-in	0:15	8:30 AM	8:45 AM
	1		Vivek	Bakshi	EUV Litho	Introduction to EUVL and EUV Sources	1:30	8:45 AM	10:15 AM
						Break	0:15	10:15 AM	10:30 AM
	2		Patrick	Naulleau	EUV Tech	EUVL Patterning and Resist	1:30	10:30 AM	12:00 PM
						Lunch Break	0:30	12:00 PM	12:30 PM
	3		Jan	van Schoot	ASML	High NA EUVL	1:30	12:30 PM	2:00 PM
						Break	0:15	2:00 PM	2:15 PM
	4		Sangsul	Lee	POSTECH	EUVL Masks	1:30	2:15 PM	3:45 PM
						Break	0:15	3:45 PM	4:00 PM
	5		Vivek	Bakshi	EUV Litho	Lithography Options Beyond High NA –Hyper NA and Blue-X	0:30	4:00 PM	4:30 PM
						Short Course Adjourned			

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
						Blue- X Technical Working Group (TWG) Meeting			
						In-person Meeting, Open to Blue-X TWG Members only			
						8:30 AM - 4:00 PM , Monday June 23, 2025, MIT LL, Boston, MA			
						Detailed Blue-X TWG Meeting Agenda will be announced in May 2025			
						Breakfast, Coffee and Check-in	1:00	8:30 AM	9:30 AM
						Technical Group Discussion and Blue-X TWG Member Presentations		9:30 AM	4:00 PM
						Partial List of Presentations: Blue-X TWG Meeting (In-Person)			
	P23 (EUVL)	Metrology	Muharrem	Bayraktar	University of Twente	2025 EUV and Source Workshop Invited Talk (Tentative Title)	0:15		
	P75 (EUVL)	Sources	Yosuke	Honda	KEK	The Must Light Source	0:15		
	P82 (EUVL)	Sources	Jackson	Williams	LLNL	EUV and plasma sources using high energy solid state λ ≈ 2 μm laser drivers	0:15		
	P83 (EUVL)	Sources	Peter	Moulton	MIT LL	Solid state laser drivers for EUV plasma sources	0:15		
	TBA	Sources	Paul	Chesler	MIT LL	Plasma Simulation for Blue-X Sources	0:15		

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
	TBA	Sources	Tommy / Nate	Sebastian / O'Connor	MIT LL	Liquid Nitrogen Droplets for Blue-X Sources	0:15		
	TBA	Sources	James	Colgan	LANL	Overview of the fundamental atomic data required for modeling the emission from Blue-X ions of interest	0:15		
						Break		4:00 PM	4:30 PM
						Joint Reception with 2025 EUVL and Source Workshop Attendees		4:30 PM	6:00 PM
Blue-X TWG Meeting Adjourned									

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Day 1: 2025 EUVL and Source Workshop									
Joint Reception: Blue- X TWG and 2025 EUVL and Source Workshop									
4:30 PM - 6:00 PM, Monday, June 23, 2025, MIT LL, Boston, MA									
						Registration and Reception		**4:30 PM**	**6:00 PM**
						Buses take attendees back to their hotels		**6:00 PM**	
Joint Reception Adjourned									

Day 2: 2025 EUVL and Source Workshop

8:30 AM - 7:00 PM, Tuesday, June 24, 2025, MIT LL, Boston, MA

Please see Abstract Book on website www.euvlitho.com for abstracts and co-author(s) information by paper #.

Session 1: Keynote 1, Session co-chairs: Mordy Rothschild (MIT LL)

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
						Breakfast, Coffee and Check-in	0:30	8:30 AM	9:00 AM
		Introduction	Vivek Bakshi / Mordy Rothschild		EUV Litho / MIT LL	Welcome and Announcements	0:15	9:00 AM	9:15 AM
1	P2	Keynote - 1	Steven	Carson	Intel	Update on High-NA EUV in process technology development	0:30	9:15 AM	9:45 AM
1	P1	Keynote - 1	Allen	Gabor	IBM	IBM Lithography Roadmap and Need for Future Lithography Tools	0:30	9:45 AM	10:15 AM
1	P3	Keynote - 1	Mark	Gouker	MIT LL	2025 EUV and Source Workshop Invited Talk (Tentative Title)	0:30	10:15 AM	10:45 AM
						Break	**0:15**	**10:45 AM**	**11:00 AM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 2: Mask 1, Session co-chairs: Marcus Benk (CXRO) and Luke Long (EUV Tech)									
2	P13	Mask - 1	Marcus	Benk	CXRO	Hyper-NA EUV Imaging, and Beyond	0:15	11:00 AM	11:15 AM
2	P11	Mask - 1	Stuart	Sherwin	EUV Tech	EUV Absorber Sidewall Metrology with EUV Scatterometry	0:15	11:15 AM	11:30 AM
2	P12	Mask - 1	Yogev	Baruch	Zeiss	Reduction of Wafer Intra-Field Overlay and CDU Residuals via laser processing of EUV Reticles	0:15	11:30 AM	11:45 AM
2	P14	Mask - 1	Luke	Long	EUV Tech	HVM-ready EUV zoneplate microscopy for mask defect review	0:15	11:45 AM	12:00 PM
						Lunch	**1:00**	**12:00 PM**	**1:00 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 3: Mask 2, Session co-chairs: Ron Levi (Corning) and Katrina Rook (Veeco)									
3	P15	Mask - 2	Ron	Levi	Corning	EXTREME ULE® for EUV Lithography reticles	0:15	1:00 PM	1:15 PM
3	P16	Mask - 2	Yunsoo	Kim	Hanyang University	Ion Implantation for Improved Etching and Optical Performance in Next-Generation EUV Mask	0:15	1:15 PM	1:30 PM
3	P17	Mask - 2	IKEBE	Yohei	Hoya	Holistic design for EUV blanks beyond 1.X nm node	0:15	1:30 PM	1:45 PM
3	P18	Mask - 2	Kevin	Lucas	Synopsys	High NA EUV design to mask stitching enablement	0:15	1:45 PM	2:00 PM
3	P19	Mask - 2	Katrina	Rook	Veeco	Advanced Ion Source & Target Developments for EUV Mask Multilayer Deposition	0:15	2:00 PM	2:15 PM
						Break	**0:15**	**2:15 PM**	**2:30 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 4: Metrology, Session co-chairs: Ahmed Diallo (PPPL)									
4	P21	Metrology	Mark	Schattenburg	MIT	High Resolution Imaging and Spectrographic Instruments for 1-10 nm X-ray Astrophysics	0:15	2:30 PM	2:45 PM
4	P22	Metrology	Brian	Simonds	NIST	Absolute Traceable Electrical Substitution Radiometers for EUV Wavelengths and Beyond	0:15	2:45 PM	3:00 PM
15	P43	Metrology	Franck	Delmotte	Université Paris-Saclay	Synthesis and metrology of Cr/Sc-based multilayer mirrors for the water window	0:15	3:00 PM	3:15 PM
Session 5: Modeling, Session co-chairs: Igor Golovkin (Prism Computations) and Jose Fonseca (FS Dynamics)									
5	P31	Modeling	Kirill	Lezhnin	PPPL	Examining Kinetic Plasma Behavior in EUVL Sources with Particle-In-Cell Simulations	0:15	3:15 PM	3:30 PM
5	P32	Modeling	Igor	Golovkin	Prism Computations	Plasma Simulations of EUV/x-ray Sources: Radiation Transport and Atomic Physics Models	0:15	3:30 PM	3:45 PM
5	P33	Modeling	Akira	Sasaki	QST	Atomic model to model EUV emission spectrum and to produce the opacity table of tin	0:15	3:45 PM	4:00 PM
						Break	**0:15**	**4:00 PM**	**4:15 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 6: Sources 1, Session co-chairs: Jens Brunne (Trumpf) and Hakaru Mizoguchi (Kyushu University)									
6	P73	Source 1	Jens	Brunne	Trumpf	The path towards 1.5kW EUV with the CO2 drive laser	0:15	4:15 PM	4:30 PM
6	P71	Source 1	Kentaro	Tomita	Hokkaido University	Increment of EUV radiation and reduction of ion energy of laser-produced Sn EUV-light-source plasmas by controlling initial plasma structure using multiple pre-pulse laser irradiations	0:15	4:30 PM	4:45 PM
6	P72	Source 1	Hakaru	Mizoguchi	Kyushu university	Plasma Dynamics and Future of LPP-EUV Source for Semiconductor Manufacturing IV	0:15	4:45 PM	5:00 PM
6	P74	Source 1	Hideyuki	Sera	Ushio	Diagnostics of Laser-assisted Discharge Tin Plasma EUV source using collective Thomson scattering	0:15	5:00 PM	5:15 PM
						Break	**0:15**	**5:15 PM**	**5:30 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 7: Poster Session, Session co-chairs: Vivek Bakshi (EUV Litho)									
						Poster Session and Reception	1:30	5:30 PM	7:00 PM
7	P101	Poster	Soyeong	Heo	Chonnam National University	Synthesis, Characterizations, and Ligand Substitution of a Non-Alkyl Tin Oxo Cluster as an Inorganic Resist for EUV Lithography			
7	P102	Poster	Seung-Yong	Baek	Chonnam National University	Improved Sensitivity of CNU-TOC-01(4C-C), a Tin-Oxo Cluster-Based EUV Inorganic Resist, via Position-Selective Purification			
7	P103	Poster	Wonchul	Kee	Chonnam National University	Development of a Monomeric Inorganic Resist (CNU-TIDO-AA) for EUV Lithography			
7	P104	Poster	Gahyun	Lee	Chonnam National University	Synthesis and Evaluation of Function-Integrated Inorganic Molecular Resists for EUV Lithography			
7	P105	Poster	Alessandro	Ruocco	FS Dynamics	Numerical simulations application in semiconductor manufacturing			
7	P106	Poster	Jochen	Viekers	ILT	Platform to study effects of EUV-induced plasmas			
7	P107	Poster	Alec	Griffith	PPPL	Laser Diagnostics for EUVL Sources at Princeton Plasma Physics Laboratory			
7	P108	Poster	Akira	Miyake	Toyama	The development of EUV and soft X-ray optical evaluation systems in TOYAMA			
7	P109	Poster	Henry	Chou	Energetiq	Energetiq New Products Poster (Tentative Title)			

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
7	P54	Poster	Nikhil	Tiwale	Brookhaven National Lab	High-sensitivity hybrid EUV resist synthesis via vapor phase infiltration			
7	P110	Poster	Stephanie	Moffitt	NIST	EUV Metrology at NIST			
7	P111	Poster	Satinder	Sharma	IIT Mandi	Engineered Hybrid Metal-Organic Clusters Resist for Next-Generation High-NA EUV Lithography			
						Buses Depart for Hotels		**7:00 PM**	

Day 3: 2025 EUVL and Source Workshop

8:30 AM - 4:45 PM, Wednesday, June 25, 2025, MIT LL, Boston, MA

Please see Abstract Book on website www.euvlitho.com for abstracts and co-author(s) information by paper #.

Session 8: Keynote 2, Session co-chairs: Carrie Huguenin (MIT LL)

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
						Breakfast, Coffee and Check-in	0:25	8:30 AM	8:55 AM
		Introduction	Vivek Bakshi / Mordy Rothschild		EUV Litho / MIT LL	Welcome and Announcements	0:05	8:55 AM	9:00 AM
8	P4	Keynote - 2	Oscar	Versolato	ARCNL	Research & roadmap for future sources of EUV light and beyond (BEUV)	0:30	9:00 AM	9:30 AM
8	P5	Keynote - 2	Debbie	Gustafson	Energetiq	We Can Make a Difference – How to Promote Women in Technology	0:30	9:30 AM	10:00 AM
8	P6	Keynote - 2	Junji	Yumoto	University of Tokyo	Development of Next-Generation Semiconductor Process Technologies for EUV and BEUV under Japan's "K Program" for Economic Security by JST	0:30	10:00 AM	10:30 AM
						Break	**0:15**	**10:30 AM**	**10:45 AM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 9: Resist and Patterning 1, Session co-chairs: Alex Robinson (IM) and Anuja DeSilva (Lam)									
9	P60	Resist and Patterning 1	Alex	Robinson	IM	The Multi-Trigger Resist - EUV Performance Update	0:15	10:45 AM	11:00 AM
9	P56	Resist and Patterning 1	Hyun-Dam	Jeong	Chonnam National University	Recent Developments and an Unexpected Discovery in Our Tin-Based Inorganic Molecular Resists for EUV Lithography	0:15	11:00 AM	11:15 AM
9	P57	Resist and Patterning 1	Chenyun	Yuan	Cornell	EUV photoresists with controlled sequences lead to improved stochastics and the discovery of a novel patterning mechanism	0:15	11:15 AM	11:30 AM
9	P58	Resist and Patterning 1	Rachel	Synder	Dupont	Next-Generation EUV Double Amplification Photoresists From Acid-Catalyzed Chain Unzipping	0:15	11:30 AM	11:45 AM
9	P59	Resist and Patterning 1	Nishiki	Fujimaki	Fujifilm	EUV NTD-CAR performance toward high-NA EUVL	0:15	11:45 AM	12:00 PM
9	P61	Resist and Patterning 1	Anuja	DeSilva	Lam	Dry Resist Patterning Readiness Towards High NA EUV Lithography	0:15	12:00 PM	12:15 PM
						Lunch	**1:00**	**12:15 PM**	**1:15 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 10: Sources 2, Session co-chairs: Jochen Viekers (ILT) and Takeshi Higashiguchi (Utsunomiya University)									
10	P77	Source 2	Takeshi	Higashiguchi	Utsunomiya University	Efficient EUV/B-EUV sources by laser irradiation schemes	0:15	1:15 PM	1:30 PM
10	P76	Source 2	Yusuke	Teramoto	Ushio	A compact laser-driven short-wavelength radiation source	0:15	1:30 PM	1:45 PM
10	P78	Source 2	Jingquan	Lin	Changchun University of Science and Technology, China	Enhancement of spectral performance in gadolinium-based BEUV sources	0:15	1:45 PM	2:00 PM
10	P79	Source 2	David	Reisman	Energetiq	SXR development for metrology, inspection, and process control using a discharge-produced plasma source	0:15	2:00 PM	2:15 PM
10	P80	Source 2	Jochen	Viekers	ILT	Laser-driven x-ray generation for industrial applications	0:15	2:15 PM	2:30 PM
						Break	**0:15**	**2:30 PM**	**2:45 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 11: Sources 3, Session co-chairs: Peter Moulton (MIT LL) and Henry Kapteyn (K&M Labs)									
11	P81	Source 3	Christian	Gaida	Active Fiber Systems GmbH	2µm fiber laser systems for next generation EUV plasma sources	0:15	2:45 PM	3:00 PM
11	P84	Source 3	Dong Gun	Lee	E-Sol	Why High-Order Harmonic Generation Is the Optimal Source Solution for EUV Mask Review Systems	0:15	3:00 PM	3:15 PM
11	P85	Source 3	Peter	Kraus	ARCNL	High-Harmonic Generation driven Extreme-Ultraviolet Scatterometry for Nanostructure Characterization	0:15	3:15 PM	3:30 PM
11	P86	Source 3	Bastian	Manschwetus	Class 5 Photonics	High repetition rate, high average power XUV sources based on High Harmonic Generation	0:15	3:15 PM	3:30 PM
11	P87	Source 3	Henry	Kapteyn	K&M Labs	Nanoscale Metrologies using Coherent EUV Sources	0:15	3:30 PM	3:45 PM
						Break and Buses Depart for Site Tours and Hotels: Energetiq Reception or MIT. Nano Tour		**4:00 PM**	

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Day 4: 2025 EUVL and Source Workshop									
8:30 AM - 7:30 PM, Thursday, June 26, 2025, MIT LL, Boston, MA									
Please see Abstract Book on website www.euvlitho.com for abstracts and co-author(s) information by paper #.									
Session 12: Keynote 3, Session co-chairs: Mordy Rothschild (MIT LL)									
						Breakfast, Coffee and Check-in	0:25	8:30 AM	8:55 AM
		Introduction	Vivek Bakshi / Mordy Rothschild		EUV Litho / MIT LL	Welcome and Announcements	0:05	8:55 AM	9:00 AM
12	P8	Keynote - 3	Bruce	Smith	RIT	EUV multilayer optimization for next-generation EUVL - 13.5nm/11.3nm high-NA and 6.6nm/WW opportunities	0:30	9:00 AM	9:30 AM
12	P7	Keynote - 3	Robert	Chau	Natcast	EUV and Non-EUV Based Lithography R&D to Extend Semiconductor Device Scaling and Improve Manufacturing Efficiency	0:30	9:30 AM	10:00 AM
						Break	**0:15**	**10:00 AM**	**10:15 AM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 13: Supplier Showcase, Session co-chairs: Jacqueline van Veldhoven (TNO) and Meng Lee (Veeco)									
13	P91	Supplier Showcase	Henry	Chou	Energetiq	Cost- Effective EUV Light Sources for High-Volume Manufacturing	0:15	10:15 AM	10:30 AM
13	P96	Supplier Showcase	Jacqueline	van Veldhoven	TNO	Studying the interaction of EUV and plasma with scanner construction materials	0:15	10:30 AM	10:45 AM
13	P92	Supplier Showcase	Matt	Hettermann	EUV Tech	Applications of EUV Metrology Tools	0:15	10:45 AM	11:00 AM
13	P93	Supplier Showcase	Jose	Fonseca	FS Dynamics	Numerical simulations for accelerating productivity and equipment design in semiconductor manufacturing	0:15	11:00 AM	11:15 AM
13	P94	Supplier Showcase	Victor	Soltwisch	PTB	About X-ray metrology and the aftermath	0:15	11:15 AM	11:30 AM
13	P95	Supplier Showcase	Andreas	Biermanns - Foeth	Research Instruments	Tools and solutions for actinic EUV metrology	0:15	11:30 AM	11:45 AM
13	P97	Supplier Showcase	Meng	Lee	Veeco	2025 EUV and Source Workshop Invited Talk (Tentative Title)	0:15	11:45 AM	12:00 PM
						Lunch	**1:00**	**12:00 PM**	**1:00 PM**
Session 14: Resist and Patterning 2, Session co-chairs: Ralph Dammel (Merck) and Chang-Yong Nam (BNL)									
14	P53	Resist and Patterning 2	Ralph	Dammel	Merck/EMD Electronics	Estimation of Resist Photospeeds for Blue-X Wavelengths	0:15	1:00 PM	1:15 PM

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
14	P51	Resist and Patterning 2	Oleg	Kostko	CXRO	Advancing EUV Photoresist Development: High-Throughput Screening of Electron-Induced Chemical Transformations	0:15	1:15 PM	1:30 PM
14	P52	Resist and Patterning 2	Myung- Gil	Kim	Sungkyunkwan University	Isomorphic molecular control of Sb based inorganic EUV photoresist for optimized photosensitivity and stability	0:15	1:30 PM	1:45 PM
14	P55	Resist and Patterning 2	Chang-Yong	Nam	Brookhaven National Lab	Organic-Inorganic Hybrid EUV Photoresists Derived from Atomic Layer Deposition Techniques	0:15	1:45 PM	2:00 PM
						Break	**0:15**	**2:00 PM**	**2:15 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 15: Optics, Session co-chairs: Torsten Feigl (optiXfab) and Marcelo Ackermann (University of Twente)									
15	P42	Optics	Donis	Flagello	Nikon Research	Beyond One-Size-Fits-All: Tailoring EUV (and BEUV) Optics for HVM Efficiency	0:15	2:15 PM	2:30 PM
15	P44	Optics	Michael	Patra	Carl Zeiss	Hyper-NA: an EUV system with a numerical aperture of at least 0.75	0:15	2:30 PM	2:45 PM
15	P45	Optics	Torsten	Feigl	optiXfab	2025 EUV and Source Workshop Invited Talk (Tentative Title)	0:15	2:45 PM	3:00 PM
15	P46	Optics	Marcelo	Ackermann	University of Twente	2025 EUV and Source Workshop Invited Talk (Tentative Title)	0:15	3:00 PM	3:15 PM
15	P41	Optics	Vladimir	Liberman	MIT LL	Advanced Blue-X Multilayer Coating Designs Strategies	0:15	3:15 PM	3:30 PM
						Break	**0:15**	**3:30 PM**	**3:45 PM**

#	Paper #	Area	Presenter (First)	Presenter (Last)	Company	Title	Duration	Start	Finish
Session 16: Resist and Patterning 3, Session co-chairs: Sascha Brose (RWTH) and Iacopo Mochi (PSI)									
16	P64	Resist and Patterning 3	Sascha	Brose	RWTH	Lab-based EUV interference lithography for large-area nanopatterning towards sub-10 nm resolution	0:15	3:45 PM	4:00 PM
16	P66	Resist and Patterning 3	Hank	Smith	MIT	Replacing EUV with X-ZPAL	0:15	4:00 PM	4:15 PM
16	P62	Resist and Patterning 3	Congque	Dinh	TEL	Advanced Coater/developer Technologies for High-NA EUV Lithography	0:15	4:15 PM	4:30 PM
16	P65	Resist and Patterning 3	Bruno	LaFontaine	CXRO	EUV Lithography at The Center for X-Ray Optics	0:15	4:30 PM	4:45 PM
16	P67	Resist and Patterning 3	Iacopo	Mochi	PSI	Development of a Next-Generation Interference Lithography End Station at the Swiss Light Source	0:15	4:45 PM	5:00 PM
16	P63	Resist and Patterning 3	Michael	Tsapatsis	John Hopkins University	Amorphous Zeolitic imidazolate Framework (aZIF) Films for Electron Beam, Extreme UV, and Beyond Extreme UV Lithography Applications	0:15	5:00 PM	5:15 PM
						Announcements	0:15	5:15 PM	5:30 PM
						Workshop Dinner	1:30	5:30 PM	7:00 PM
						Buses Depart for Hotels		**7:00 PM**	
Workshop Adjourned									